Electronic Supplementary Material (ESI) for Nanoscale. This journal is © The Royal Society of Chemistry 2021

## **Supporting Information**

## Phase transition and topological transistors based on monolayer Na<sub>3</sub>Bi nanoribbons

Bowen Shi<sup>1</sup>, Hao Tang<sup>1</sup>, Zhigang Song<sup>2</sup>, Jingzhen Li<sup>1</sup>, Lianqiang Xu<sup>3</sup>, Shiqi Liu<sup>1</sup>, Jie Yang<sup>1</sup>, Xiaotian Sun<sup>4</sup>, Ruge Quhe<sup>5</sup>, Jinbo Yang<sup>1,6,7</sup>, and Jing Lu<sup>1,6,7,8\*</sup> <sup>1</sup> State Key Laboratory for Mesoscopic Physics and Department of Physics, Peking University, Beijing 100871, P. R. China <sup>2</sup> Computational Research Division, Lawrence Berkeley National Laboratory, Berkeley, CA 94720, USA <sup>3</sup> School of Physics and Electronic Information Engineering, Engineering Research Center of Nanostructure and Functional Materials, Ningxia Normal University, Guyuan, Ningxia 756000, P. R. China <sup>4</sup>College of Chemistry and Chemical Engineering, and Henan Key Laboratory of Function-Oriented Porous Materials, Luoyang Normal University, Luoyang 471934, P. R. China <sup>5</sup> State Key Laboratory of Information Photonics and Optical Communications and School of Science, Beijing University of Posts and Telecommunications, Beijing 100876, P. R. China <sup>6</sup> Collaborative Innovation Center of Quantum Matter, Beijing 100871, P. R. China <sup>7</sup> Beijing Key Laboratory for Magnetoelectric Materials and Devices (BKL-MEMD), Beijing 100871, P. R. China <sup>8</sup> Peking University Yangtze Delta Institute of Optoelectronics, Peking University, Nantong 226010, P. R. China \*Corresponding author: jinglu@pku.edu.cn



**Fig. S1.** Band structures of the (a) 3.95-nm width ML Na<sub>3</sub>Bi ZNR and (b) 3.97-nm width ML Na<sub>3</sub>Bi ANR with 0.02 and 0.03 eV whole bandgap, respectively. The Fermi level is set to 0.



**Fig. S2.** Band structure projected on the (a) middle atoms, (b) edge atoms, (c) left atoms, and (d) right atoms of the 1.28-nm width ML Na<sub>3</sub>Bi ZNR. The red/blue dots in the band structure represent the spin-up/spin-down states. The Fermi level is set to 0.



**Fig. S3.** Bulk bandgaps of the (a) 1.26, (b) 2.16, (c) 6.85, (d) 1.28, (e) 2.20, and (f) 6.99nm width ML Na<sub>3</sub>Bi ZNRs under different  $D_{\text{ext}}$ . (d), (e), and (f) have 2% strain applied in the width direction of (a), (b), and (c), respectively.



Fig. S4. Spin-resolved band structures projected on the middle atoms of the 2.20-nm width ML Na<sub>3</sub>Bi ZNR under different  $D_{ext}$ . The blue dots represent the spin-up states and the red dots represent the spin-down states. The number of states is reflected in the size of the dots.



Fig. S5. Spin-resolved band structures projected on the middle atoms of the 6.85-nm width

ML Na<sub>3</sub>Bi ZNR under different displacement electric fields. The middle atoms are shown in Fig. 3. The blue dots represent the spin-up states and the red dots represent the spindown states. The number of states is reflected in the size of the dots.



**Fig. S6.** Local device density of states (LDOS) of the ML Na<sub>3</sub>Bi NR topological transistor at  $V_{\text{bias}} = 0$  V. (a) ~ (c) and (e) ~ (g) are the LDOS of the on-state ( $V_{\text{diff}} = 11$  V), and off-state ( $V_{\text{diff}} = 24$  V). (a, e), (b, f), and (c, g) represent the states contributed by all the atoms, the middle atoms, and the edge atoms (as shown on the top), respectively. The solid vertical black lines divide the device into three parts: source, channel, and drain. (d) and (h) is the transmission spectrum of  $V_g = 11$  V and  $V_g = 24$  V, respectively. The dash horizontal black/red lines represent the bias window in the LDOS/ transmission spectrum. The yellow, blue, and white atoms represent the Na, Bi, and H, respectively.

In the simplest model, the transmission probability of a free electron (hole) going through a limited height barrier is<sup>1</sup>:

$$T = \frac{4k^2k'^2}{(k^2 - k'^2)^2\sinh^2(k'a) + (k^2 - k'^2)^2\cosh^2(k'a)}$$

$$\approx \frac{16E(V-E)}{V^2} \exp\left(-2\sqrt{\frac{2m^*(V-E)}{\hbar^2}a}\right)$$

where  $k = \frac{\sqrt{2m^*E}}{\hbar^2}$ ,  $k' = \frac{\sqrt{2m^*(V-E)}}{\hbar^2}$ ,  $\sinh(k'a) = \frac{e^{k'a} - e^{-k'a}}{2}$ ,  $\cosh(k'a) = \frac{e^{k'a} + e^{-k'a}}{2}$ . a is the

length of the barrier. For electrons,  $m^*$  is the electron effective mass, *E* is the Fermi energy of the source, and *V* is the energy of the conduction band minimum (CBM). For holes,  $m^*$  is the hole effective mass, *E* is the Fermi energy of the drain, and *V* is the energy of the valance band maximum (VBM).



Fig. S7. Schematic diagram of a free electron/hole tunneling through a finite height barrier under an infinitesimal bias voltage. The voltage of the source  $V_{\text{source}} < 0$  and the voltage of the drain  $V_{\text{drain}} > 0$ . The dash-dot line is the Fermi level.

## Reference

1. SZE, S. M., *Physics of Semiconductor Devices*. John Wiley & Sons, Inc.: Hoboken, NJ 07030, USA, 2021.